

Mechanical Behavior and Active Deformation Mechanisms in Thin Film Mg

John Sharon^{a,b}, Marc Legros^c, Yong Zhang^b, Kevin Hemker^b

^aSandia National Laboratories, Albuquerque, NM, USA

^bJohns Hopkins University, Baltimore, MD, USA

^cCEMES-CNRS, Toulouse, France



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Background & Motivation





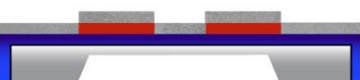


- Interest in Mg has gained traction for application in
 - Light weight structural alloys, low density but pure Mg relatively weak
 - Hydrogen storage (metal hydrides) for alternative energy
- Possible improvements from length scale reduction
 - Small grains → Hall-Petch strengthening
 - Small thickness → Shorter pathways for improved diffusion

KEY QUESTIONS

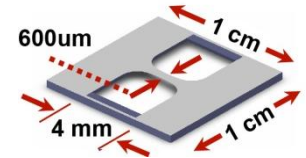
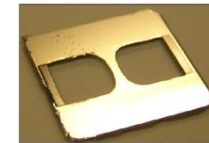
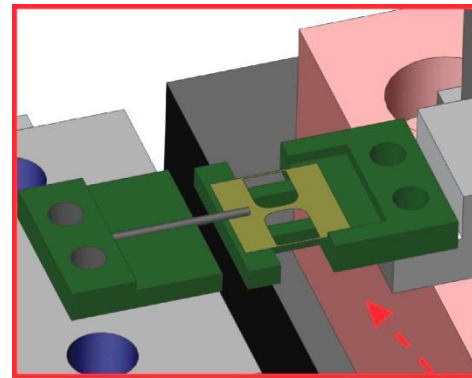
- How do small grains affect the mechanical properties of Mg?
- What deformation mechanisms are active?

Film Synthesis & Testing

Fabrication Flow

- Nitride
- 
- (1) Double side polish <100> Si wafer w/ nitride
- 
- (2) Open window on backside to expose Si
- 
- (3) Etch from backside w/ KOH; thin window
- 
- (4) Pattern resist on frontside w/ tensile geometry
- 
- (5) Physical vapor deposition of thin film
- 
- (6) Lift-off, remove resist + extraneous metal
- 
- (7) Remove Si under gauge w/ XeF₂

Mechanical Testing



Camera for strain measurement
via digital image correlation

10g Load cell

5-axis stage to
facilitate alignment

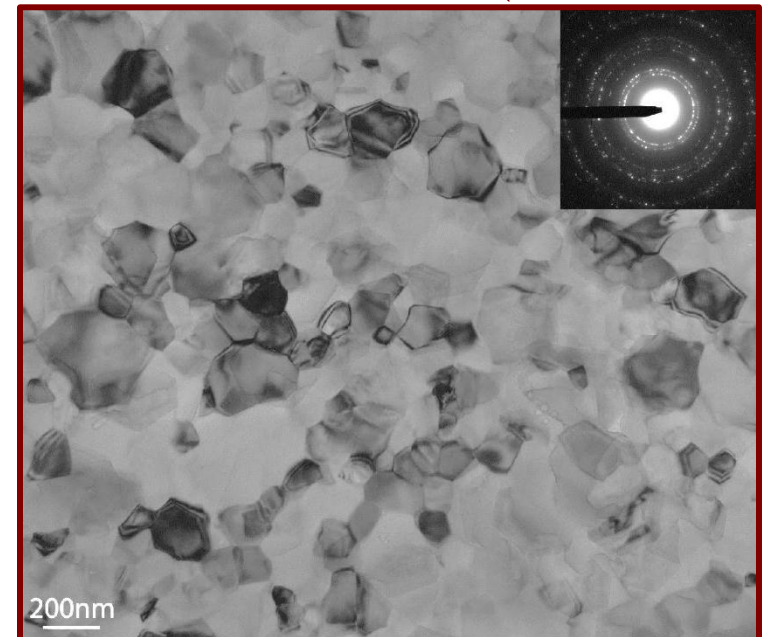
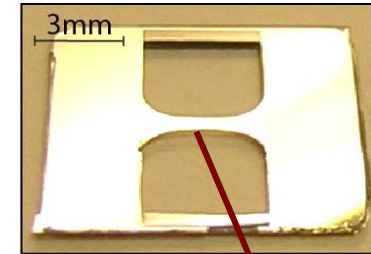
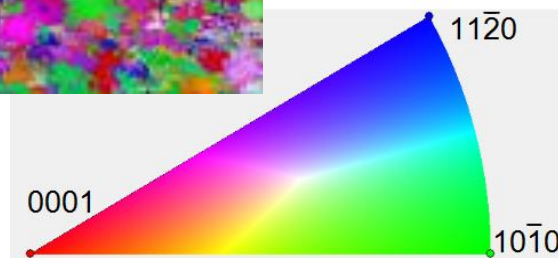
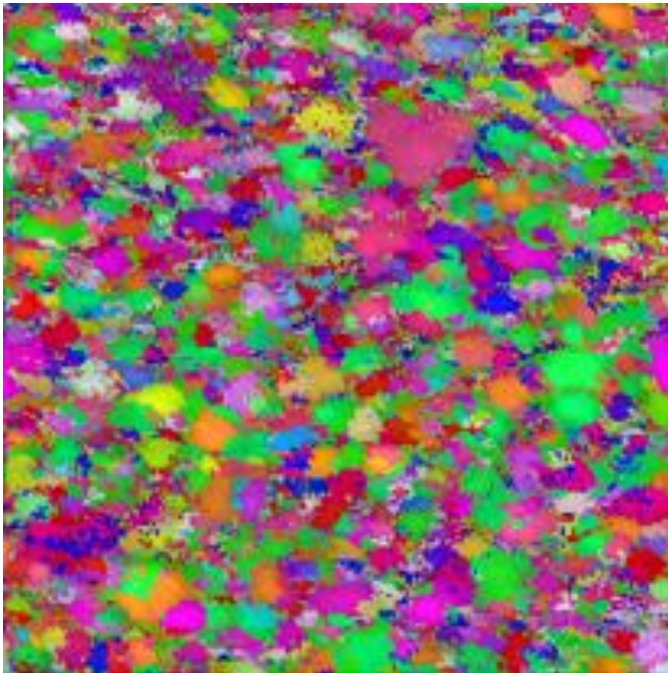
Linear actuator

Air bearing to
minimize friction

D.S. Gianola, et. al ; TMS Letters; 1 (2004)

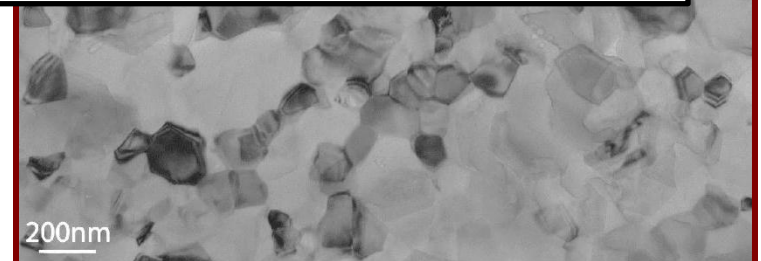
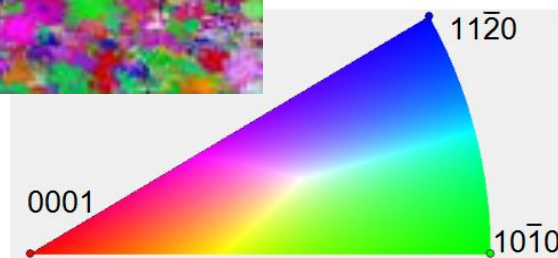
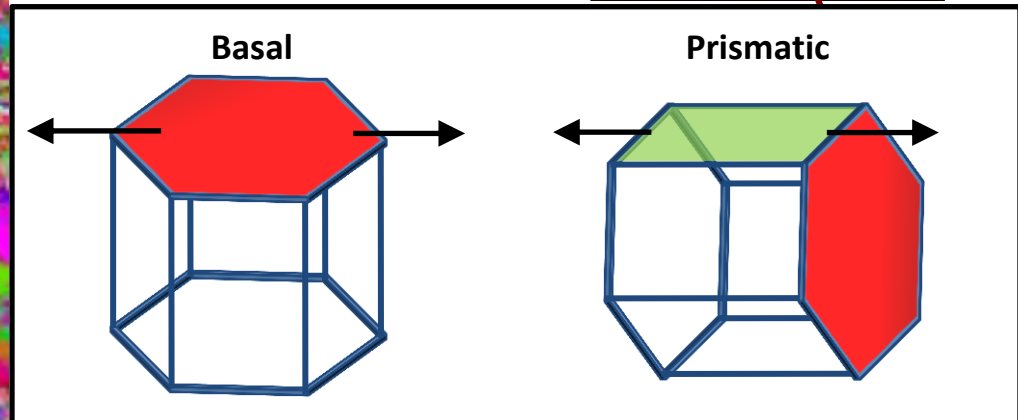
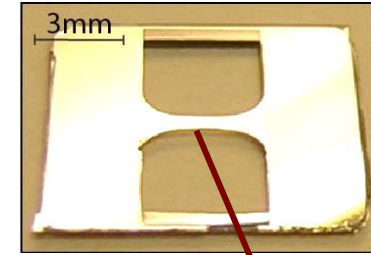
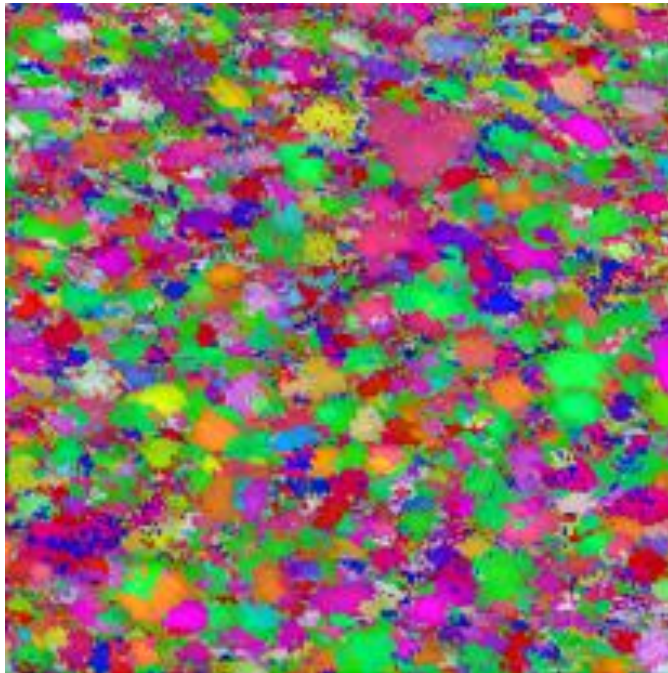
As-deposited Test Specimens

- 250nm thick films, 99.999% pure Mg e-beam evaporated under a base pressure of 8×10^{-7} Torr
- Dislocation free grains, 197nm in size

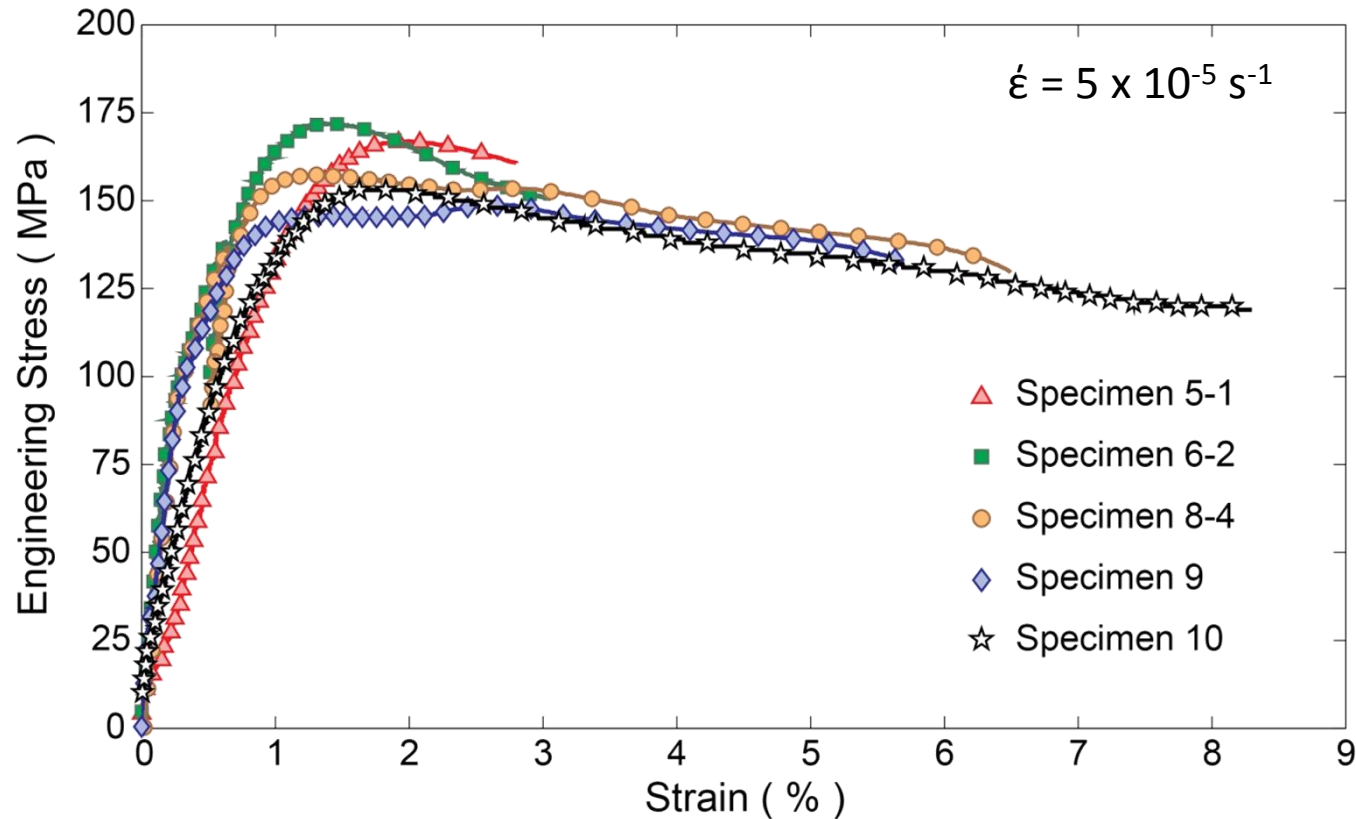


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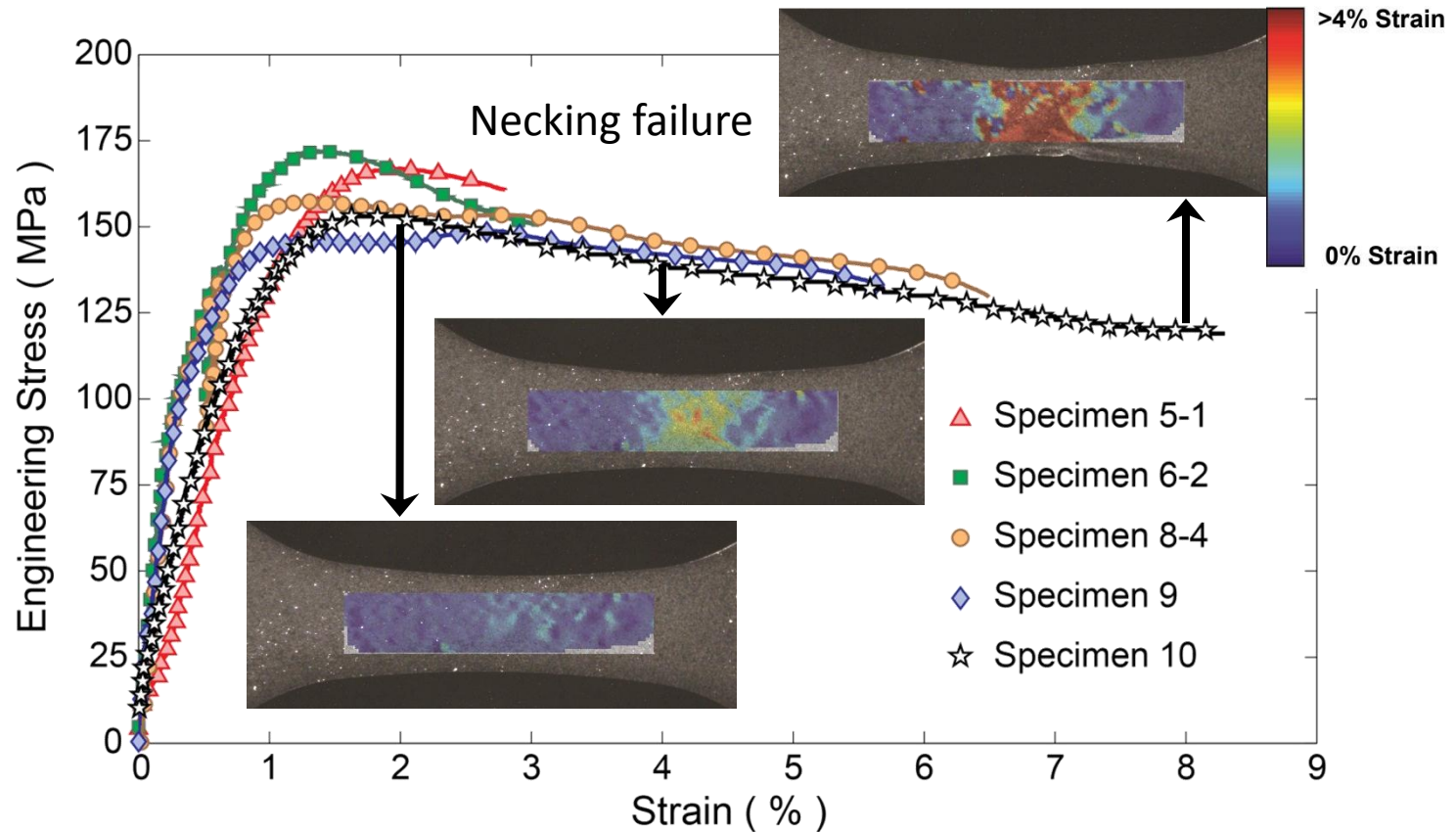


Mechanical Response



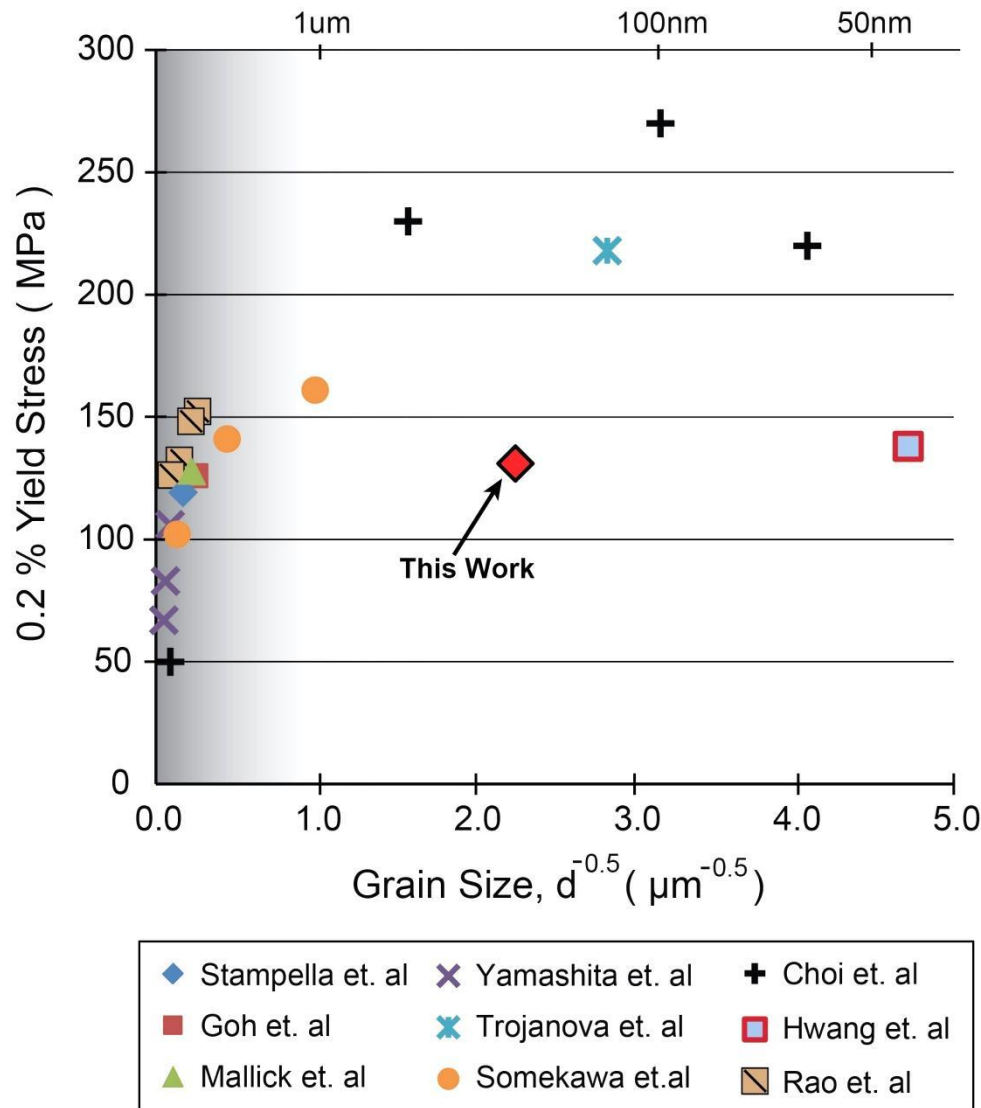
- Response similar to coarse grained Mg
 - Strengths of 160-195 MPa and elongations of 3 – 15%

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Strengthening ?



➤ “Bulk” yield point for the Mg films of this study

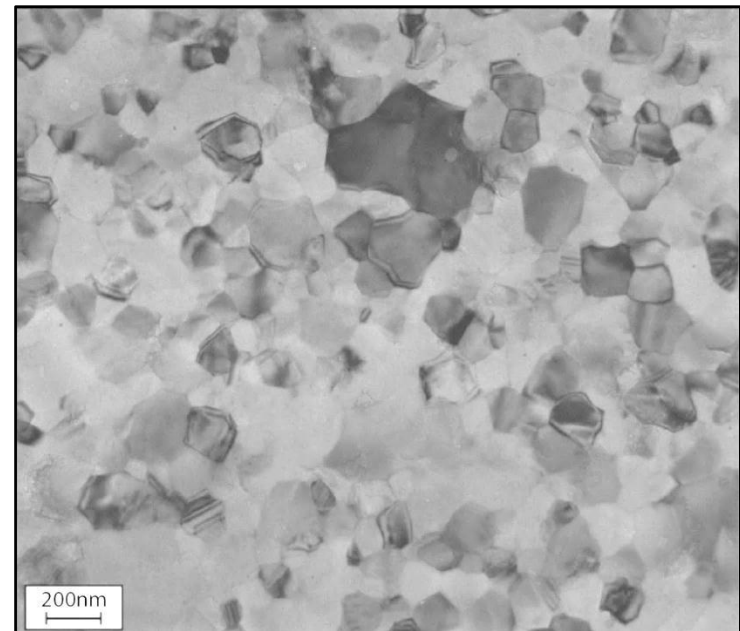
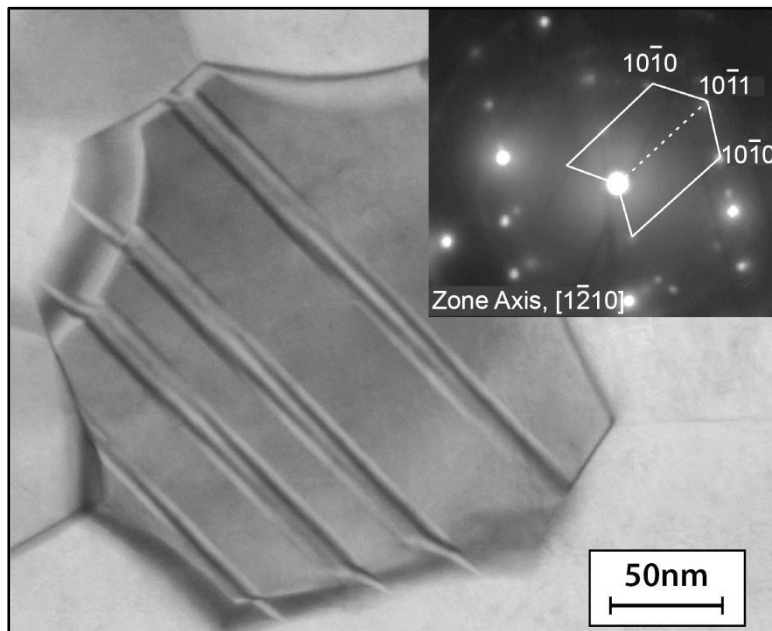
➤ Yield stress affected by

- Purity
- Texture
- Processing

➤ Differences in these factors preclude a direct comparison of all data

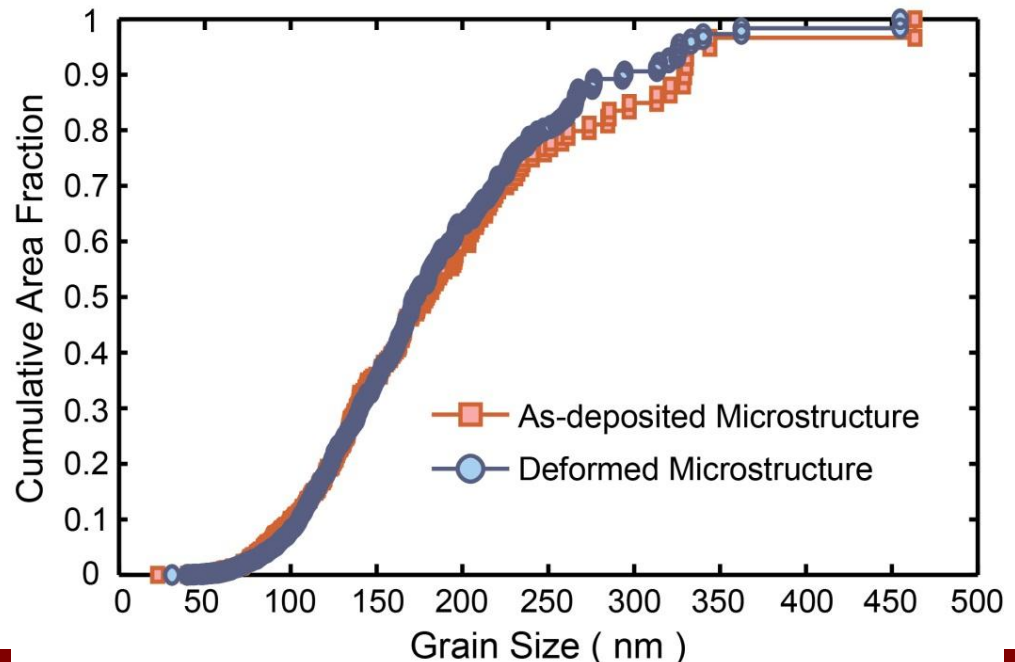
Deformation Mechanisms

- No storage of dislocations
 - Possible nucleation & absorption of dislocations at GBs
- $\{10\bar{1}1\} \langle 10\bar{1}2 \rangle$ twins
 - Deformation twins on pyramidal plane, bulk like yielding not likely from this twin system as Basal, $\tau_{\text{crss}} < \text{Prismatic}, \tau_{\text{crss}} < \text{Pyramidal}, \tau_{\text{crss}}$



Deformation Mechanisms

- No change in the grain size, no extensive GB migration or rotation events
- GS distribution reveals many grains \approx film thickness,
 - Grains with $\langle 10\bar{1}1 \rangle$ normal to film surface would have ~ 50 MPa of resolved shear on basal plane (Basal, $\tau_{crss} = 0.77$ MPa)
 - Yielding of such unconstrained grains will manifest on stress-strain response



Summary

- At 200nm GS, twinning is active with a lack of dislocation pile up
- “Bulk” yield point stems from yielding of grains spanning the full film thickness

Future Work

- In-situ TEM experiments to determine extent of dislocation and GB related processes
- Explore impact of purity and oxide on strength